

AZ 1505 – run sheet

Merck (AZ Electronic Materials)

nanyte.com/photoresists/az-1505 · last updated 2026-07-26

Thickness: 0.6–1.6 μm

Softbake: 90–110 °C

Post-exposure bake: 105–115 °C

Develop: Developer AZ 300MIF, AZ 726MIF, AZ 917MIF, or AZ 400K ·
Dilution AZ 400K used 1:4 for tank immersion; dilution of the
MIF developers is not stated in this datasheet. · Time 60 s

Hardbake: 100–110 °C